

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1448/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)			Complete If Known	
			Application Number	10/597,199-Conf. #7625
Sheet 1 of 1			Filing Date	July 14, 2006
			First Named Inventor	Karsten Buse
			Art Unit	NMA 1792
			Examiner Name	Not Yet Assigned - Hiteshew
			Attorney Docket Number	20811/0204481-USO

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (If known)			
/F.H./	AA*	US-3,700,912	10-24-1972	Glass et al.	
/F.H./	AB*	US-3,932,299	01-13-1976	Phillips	
/F.H./	AC*	US-4,398,248	08-02-1983	Holman	
/F.H./	AD*	US-5,902,519	05-11-1999	Stoll	
/F.H./	AE*	US-20020088986-A1	11-25-2002	Stoll <i>07-2002</i>	
/F.H./	AF*	US-20030084294-A1	04-03-2003	Kitamura et al.	
/F.H./	AG*	US-6,670,079	12-30-2003	Kitamura et al.	
/F.H./	AH*	US-5,904,912	05-18-1999	Kitamura et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁴
		Country Code ² -Number ³ -Kind Code ³ (If known)				
/F.H./	BA	DE-10300080	07-22-2004	Deutsche Telekom Ag		✓

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 809. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. *CITE NO.: Those application(s) which are marked with an single asterisk (*) next to the Cite No. are not supplied (under 37 CFR 1.98(a)(2)(II)) because that application was filed after June 30, 2003 or is available in the IFW. ¹ Applicant's unique citation designation number (optional). ² See Kind Codes of USPTO Patent Documents at www.uspto.gov or MPEP 801.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.18 if possible. ⁶ Applicant to place a check mark here if English language Translation is attached.

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			T ⁷
/F.H./	CA	A.A. BUKHARAEV et al.: "Investigation of Iron Impurity centres in lithium niobate", Fizika Tverdogo Tela, USSR, Feb. 1976, ISSN 0367-3294, Soviet Physics - Solid State, USA, ISSN 0038-5854, XP-002320127 (1 page).			
/F.H./	CB	K. BUSE et al.: "Development of thermally fixed holograms in photorefractive lithium-niobate crystals without light", Optical Materials 18 (2001), Elsevier Science B.V., pp. 17-18 (2 pages).			
/F.H./	CC	K. BUSE: "Light-induced charge transport processes in photorefractive crystals II: Materials", Applied Physics B (Lasers and Optics) Vol. 64, 1997, Springer-Verlag, pp. 391-407 (17 pages).			
/F.H./	CD	A. DHAR: "Optical properties of reduced lithium niobate single crystals", Journal of Applied Physics 68 (1990 1 December, No. 11, New York, pp. 5804-5809 (6 pages).			
/F.H./	CE	L. GALAMBOS et al.: "Doubly doped stoichiometric and congruent lithium niobate for holographic data storage", Journal of Crystal Growth 229 (2001), Elsevier Science B.V., pp. 228-232 (5 pages).			
/F.H./	CF	N. Y. KAMBER et al.: "Threshold effect of incident light intensity for the resistance against the photorefractive light-induced scattering in doped lithium niobate crystals", Optics Communications 176, 15 March 2000, Elsevier Science B.V., pp. 91-96 (6 pages).			
/F.H./	CG	T. ZHANG et al.: "Optical damage resistance of In:Fe:LiNbO ₃ crystals related to the defect structure", Materials Letters 58 (2004), science direct, Elsevier B.V., pp. 3074-3078 (5 pages).			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 809. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant to place a check mark here if English language Translation is attached.

Examiner Signature	/Felisa Hiteshew/	Date Considered	01/18/2008
--------------------	-------------------	-----------------	------------